

Advanced PECVD-SiN	Date	wafer#	LPD before	LPD after 5min pump down	LPD count prior deposition (SiN coat 10min, loaded wafer,5min sitting in chamber)	LPD after SiN dep.	Thickness	Index
	5/16/12	wafer1	249	not done	not done	1349	966.02	n=1.993
		wafer2	356	not done	not done	2851	3059.58	n=1.992
	5/21/12	wafer3	139	211	not done	432	1008.86	n=1.993
		wafer4	86	182	not done	487	983.05	n=1.994
SiO2coat/SiN dep*	*5/23/12	wafer5	387	343	402	590	963.19	n=1.988**
		wafer6	107	209	217	275	957.2	n=1.990**
Comments:	* SiO2 coat, SiN deposition!							
	** changed index a little bit							
Conclusion:	Increased particle count in SiN films!							
	6/4/12	wafer8	512	555	not done	630	988.83A	n=1.993
		wafer9	285	261	not done	473	976.63A	n=1.991
	6/14/12	wafer10	344	210	not done	2670	2980.90A	n=1.997
		wafer11	165	121	not done			
		wafer12	212	142	not done			